Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L16	1	(enlarg\$3 and pattern and expos\$4 and mask and space and resiz\$3). clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON ·	2007/11/13 10:37

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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	573	(((second third) with (\$5mask (photo adj mask) reticle)) same (mask photomask (photo adj mask) reticle) with (align\$5 overlay (over adj lay\$3))) and ((enlarg\$3 grow\$3 stretch\$3) with (pattern)) and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 09:45
L5	81	(((enlarg\$3 resiz\$3 (siz\$3 near2 (fix\$3 correct\$3)) increas\$3 amplif\$8 magnif\$8) near5 (lin\$3 pattern layout margin "cd" (critical near (dimension measurement features)) thin fine width\$3 spac\$3 feature))) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near2 (photomask (photo adj (mask reticle)) mask reticle)) and (((complementary trim\$4 (multi adj phase near transistion)) near2 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) same (photomask (photo adj (mask reticle)) mask reticle)) and ((photomask (photo adj (mask reticle)) mask reticle) same ((opc (optical with (correct\$3 effect\$3))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 09:52

L6	420	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 augment\$5 amplify\$8 magnif\$8) with (lin\$3 margin cd (critical near3 (dimension measurement features)) thin fine width\$3 spac\$3 densit\$3 feature)) and ((proximity near5 (effect\$3 correct\$4)) or ope or ppc) and ((opc (optical with (correct\$3 effect\$3)))) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3 cd (critical near3 (dimension\$3 measurement	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:06
L7	3	feature)))) (((mask pattern exposure reticle) near data) with (resiz\$3 enlarg\$3 (re adj siz\$3))) and (opc (optical with proximity with correction)) and ((reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) near5 (width pitch density spac\$3) with pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:07
L8	151	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 expand\$3 broaden\$3 add\$3 augment\$5 expansion maximize maximum grow\$3 stretch\$3 amplify magnif\$8) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature)) same (rule guideline constraints parameter predetermined (guide adj line) specification requirements conditions)) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((opc ope ret ppc (proximity near2 (correction effect)) (resolution near2 enhancement))) and ((lin\$3 with (spac\$3 densit\$3 width)) same pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:29

L9	40	((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 grow\$3 stretch\$3 increas\$3 magnif\$8 larg\$3)) and (pattern with (transfer\$5 expos\$5)) and (first with (\$5mask (photo adj (mask reticle)) reticle) with (width densit\$3 pitch spac\$3)) and (second with (\$5mask (photo adj (mask reticle)) reticle) with (correspond\$5 align\$5 equivalen\$3 complementary matching overlay\$3 (over adj lay\$3)) with (first with (\$5mask (photo adj (mask reticle)) reticle))) and (pattern with (rules specification constraint margin guideline (guide adj line))) and (reduc\$5 decreas\$3 shrink\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:25
		diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3) and (opc or (proximit\$3 near correct\$3) ret (enhancement with technique) (resolution with enhancement))				
L10	133	((minimum minimal min) with (space spacing width)) and ((enlarge\$4 grow\$3 stretch\$3) with (pattern mask photomask (photo adj mask))) and (align\$5 overlay\$3 (over adj lay\$3)) and (mask with set) and ((select\$3 with expos\$5))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:28

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L11		((((mask pattern photomask (phot adj mask) exposure reticle) near data) or pattern) with (resiz\$3 enlarg\$3 grow\$3 stretch\$3 increas\$3 magnif\$8 larg\$3)) and (pattern with (transfer\$5 expos\$5)) and (first with (\$5mask (photo adj (mask reticle)) reticle) with (width densit\$3 pitch spac\$3)) and (second with (\$5mask (photo adj (mask reticle)) reticle) with (correspond\$5 align\$5 equivalen\$3 complementary matching overlay\$3 (over adj lay\$3)) with (first with (\$5mask (photo adj (mask reticle)) reticle))) and (pattern with (rules specification constraint margin guideline (guide adj line))) and (reduc\$5 decreas\$3 shrink\$3 diminish\$3 lessen\$3 truncat\$5 cutback) with (width pitch densit\$3 spac\$3) and (opc or (proximit\$3 near correct\$3) ret (enhancement with technique) (resolution with enhancement)) and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:27
L12	115	((minimum minimal min) with (space spacing width)) and ((enlarge\$4 grow\$3 stretch\$3) with (pattern mask photomask (photo adj mask))) and (align\$5 overlay\$3 (over adj lay\$3)) and (mask with set) and ((select\$3 with expos\$5)) and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:28
L13	90	(((enlarg\$3 resiz\$3 (re adj siz\$3) increas\$3 expand\$3 broaden\$3 add\$3 augment\$5 expansion maximize maximum grow\$3 stretch\$3 amplify magnif\$8) with pattern with (lin\$3 margin thin fine width\$3 spac\$3 densit\$3 feature)) same (rule guideline constraints parameter predetermined (guide adj line) specification requirements conditions)) and ((first primary initial) near4 (photomask (photo adj (mask reticle)) mask reticle)) and (((second trim\$4 (multi adj phase near transistion)) near4 mask)) and ((opc ope ret ppc (proximity near2 (correction effect)) (resolution near2 enhancement))) and ((lin\$3 with (spac\$3 densit\$3 width)) same pattern) and @ad<"20040325"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/11/13 10:32